

ABSTRACT

The present invention provides a substrate cleaning apparatus which allows an end face and/or a bevel face of a substrate to be scrub-cleaned in a simple and effective manner. The apparatus comprises a plurality of rotatable substrate rotating rollers 12 and 14 for gripping the periphery of a substrate and rotating the substrate, a cleaning roller 48 capable of rotating and having a cleaning member 52 which is to be brought into contact with an end face and/or a bevel face of the substrate so as to apply scrub-cleaning to the end face and/or the bevel face, and a power transmission mechanism 64 for transmitting a rotating force of the substrate rotating roller 14 to the cleaning roller 48 so as to rotate the cleaning roller 48.